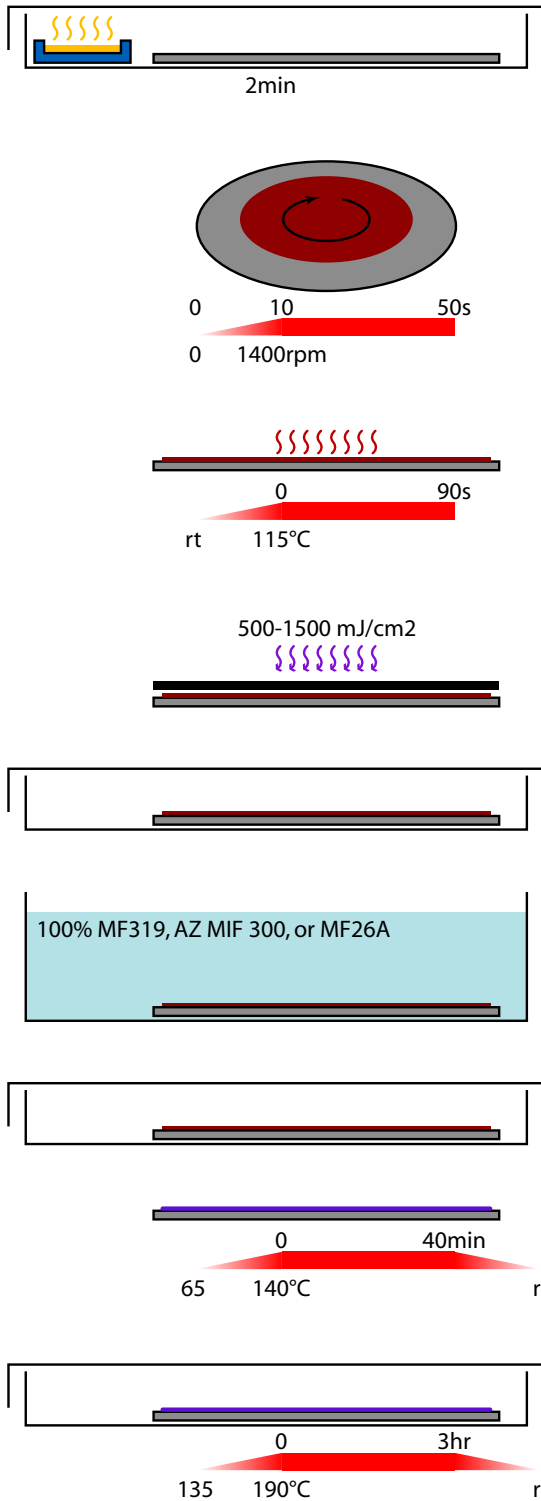


SPR Photolithography



HDMS Prime

Spin coat

Soft Bake

UV Expose

Hold >= 1hr, RT

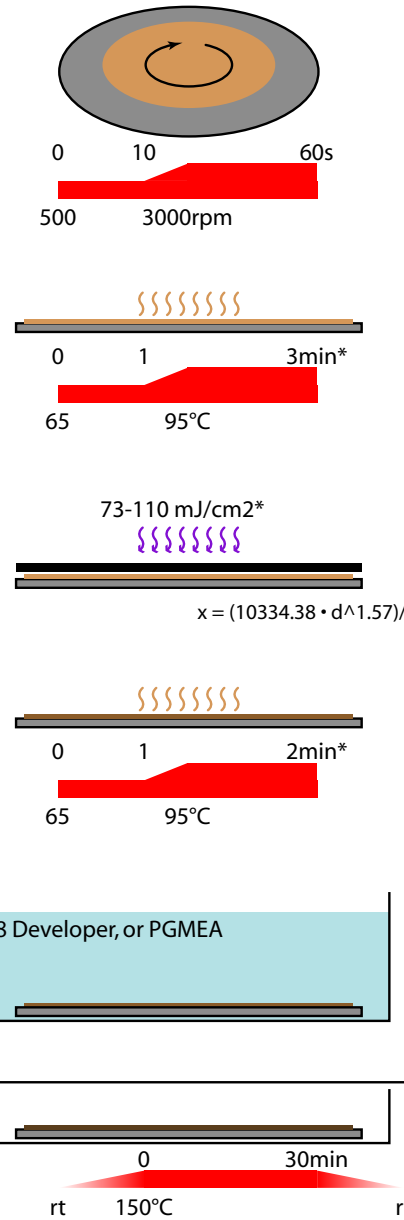
Develop

Hold >= 1hr, RT

Reflow

Hard Bake

SU-8 Photolithography



Spin coat

Soft Bake

UV Expose

PE Bake

Develop

Hard Bake